

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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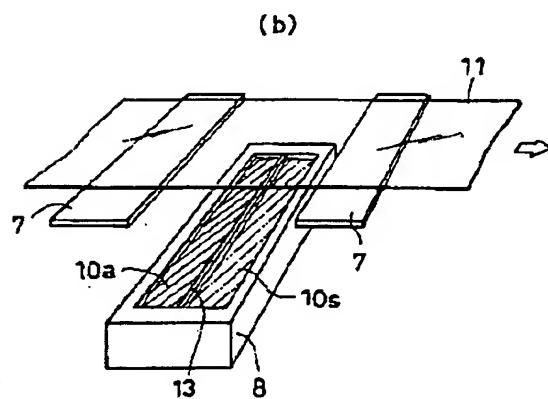
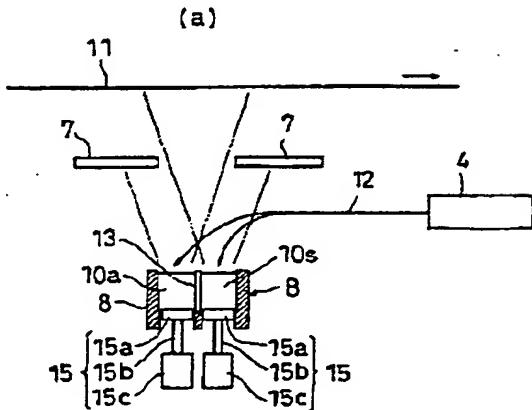
APPLICATION DATE : 13-12-99  
 APPLICATION NUMBER : 11352541

APPLICANT : TOYOB0 CO LTD;

INVENTOR : IZEKI SEIJI;

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TITLE : VACUUM EVAPORATION SYSTEM



ABSTRACT : PROBLEM TO BE SOLVED: To provide a vacuum evaporation system capable of forming a mixture film composed of dissimilar components and having high uniformity on an object to be subjected to vapor deposition.

SOLUTION: A mixture film composed of dissimilar elements can be formed on a film 11 traveling in a vacuum chamber. A crucible 8 having a thin partition 13 capable of assorting different kinds of evaporation materials 10 so as to hold these evaporation materials 10 in assorted state and an electron gun 4 for heating the evaporation materials 10 and evaporating them by heating are provided. Further, the partition 13 in a material holding means 10 is disposed in such a way that its longitudinal direction becomes nearly orthogonal to the traveling direction of the film 11.

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